

AMENDMENTS TO THE SPECIFICATION

Please replace the full paragraph on page 5 of the translated specification filed on May 17, 2004, with the following amended paragraph:

The method of which the sequence is illustrated schematically in fig. 1 is based on superimposing wavefronts by means of a phase shifting interferometry or Moiré measuring technique, forming a corresponding superimposition pattern, also referred to as an interferogram in the present case. The interfering wavefronts can, for example, be produced in an interferometer or by means of diffraction at Moiré grating structures. The method may be used in particular for the highly precise measurement of high-resolution imaging systems with regard to imaging errors, such as aberrations or distortion errors. The method can be used specifically for highly accurate imaging error determination in high-resolution projection objectives in microlithographic projection exposure installations, for which purpose appropriate apparatus is known in the prior art and therefore requires no further explanation, see for example, measurement apparatus based on shearing interferometry, as disclosed in the laid-open specification DE 101 09 929 A1, which corresponds to US 2002/0001088A1 and the German patent application 102 17 242.0, which corresponds to US 2005/0264827A1, from the applicant, which is not a prior publication. In such measuring apparatus, the optical imaging system to be measured functions as an object, so that the object wavefront supplied by it carries the imaging error information which then, following superimposition of the object wavefront with the reference wavefront, can be extracted from the superimposition pattern as object-induced phase difference information.